

Gas Plasma Cleaners | Economic, Low-frequency

PM100

Made in
Japan

Low frequency output	Low-frequency, high-voltage power supply	Reaction chamber	I.D 100mm×L160mm
----------------------	--	------------------	------------------

A simple plasma device that uses oxygen as the process gas.

Overview

- A barrel-type chamber generates plasma uniformly throughout the chamber.
- The system produces a gentle plasma using low-frequency power.
- Suitable for biochemical applications.
- Uses oxygen as the process gas.

Application

- Biochemical applications (e.g., organic membrane treatment on glass substrates).
- Cleaning of glassware (sterilization).
- Cleaning of sample holders for TEM/SEM/FIB systems, etc.
- Treatment of sensor probes used in analytical instruments.
- Accelerated testing of coated films.
- Bonding of PDMS chips to glass or PDMS plates.
- Degradation and accelerated testing of coated films, etc.



Chamber



Specifications

Model	PM100	
Plasma source	Low-frequency, high-voltage power supply	
Gas Flowmeter	Oxygen gas, flow rate 30 - 300 mL / min	
Reaction chamber	I.D 100mm×L160mm	
Exterior dimensions / Weight	W310mm×D300mm×H448mm / Approx. 16kg	
Utility	Power supply (50/60Hz) *	Single phase AC100V 10A
	Vacuum pump connection port	O.D 15mm with hose fitting (Recommended pump exhaust speed 30L / min)
	Gas connection port	O.D 6.35mm with hose fitting

* Voltage modifications other than the listed specifications are also available. Please contact us for details.

1 Sterilizers

2 Granulation and Spray Dryers

3 Furnaces

4 Ovens

5 Incubators

6 Plasma Equipment

7 Water Purifiers

8 Baths

9 Water Circulators

10 Rotary Evaporators

11 Stirrers & Shakers

12 Options